

BENEQ TFS500

The Beneq TFS500 is our most diverse research model, proven as a versatile tool for the most demanding R&D projects and batch processing. The TFS500 is the perfect tool for scaling R&D efforts and ramping into an ALD pilot production phase.



Example applications include:

- Pt ALD on nanotubes for photocatalysis
- NSilver anti-tarnish coatings for coins and jewelry
- Double-sided optical coating of highly curved lenses

SCALABLE: TFS500 maintains all the flexible perks of the TFS200 but on a bigger scale. A larger chamber enables deposition on new substrates, like 300 mm wafers, and the processing of more sizable batches of 3D objects.

ERGONOMIC: A front-mounted loading door and external precursor lines make depositions in the TFS500 easily adjustable, accessible and with quick turnaround times.

INTEGRATABLE: Beneq TFS500 can be seamlessly integrated with a large glove box and manual load lock for additional wafer processing. Plasma-enhanced ALD is available, as well as custom reaction chamber designs for specific substrate or application needs.



BENEQ TFS500 Specifications

PROCESS TYPE	Thermal ALD Plasma-Enhanced ALD
USAGE	Research & Development Production
INTEGRATION	Stand-alone, Cluster, Glovebox, Loadlock
DIMENSIONS	1600 × 900 × 1930 mm
TEMPERATURE RANGE	25–500 °C
SUBSTRATE TYPE	Up to 300 mm wafers 3D parts up to 300 × 420 mm

Beneq Research Equipment

Beneq maintains the largest install base of ALD research equipment for academic research and corporate R&D. We are dedicated to providing customers with premium, versatile research equipment to meet demanding lab environments and enable cutting-edge results.



Beneq TFS200

The most flexible and highly customizable ALD research platform.



Beneq TFS500

Diverse configurations available for single and batch processes.



Beneq R2

Compact, scalable, and affordable to start your ALD journey.

